

IN THE SPECIFICATION:

Please rewrite the paragraph beginning on page 11, line 4, so that it reads as follows:

In Fig. 6, a first substrate 600 and a second substrate 670 opposite the first substrate 600 are provided. The first substrate 600 can be a TFT array glass substrate and the second substrate 670 can be a glass substrate. Then, a first color filter 610 having uneven surface is formed on the first substrate 600. The first color filter 610 may have three color regions, such as red (R), green (G), and blue (B). As a demonstrative example, referring to Fig. 6, a red (R) pattern comprising a red major portion 691 in the red region, and red bumps 692 and 693 in the green region and the blue region is formed on part of the first substrate 600 by a patterning process. Then, a green (G) pattern is formed on part of the first substrate 600 and part of the red (R) pattern by a patterning process, in which the green pattern comprises a green major portion 694 covering the red bumps 692 in the green region to have an uneven surface, and green bumps 695 on the major portion of the red pattern 691 in the red region. Then, a blue (B) pattern is formed on part of the first substrate 600 and part of the red (R) pattern by a patterning process. Thus, a partial surface of the first color filter 610 with bumps is obtained.

Please rewrite the paragraph the paragraph beginning on page 12, line 23, so that it reads as follows

In Fig. 7, a first substrate 700 and a second substrate 770 opposite thereto are provided. The first substrate 700 can be a thin film transistor (TFT) array substrate and the second substrate 770 can be a glass substrate. Then, a first color filter 710 having uneven surface is formed on the first substrate 700. The first color filter 710 may have

three color regions, such as red (R), green (G), and blue (B). As a demonstrative example, referring to Fig. 7, a red (R) pattern, comprising a red major portion 791 in the red region, and red bumps 792 and 793 in the green region and the blue region, is formed on part of the first substrate 700 by a patterning process. Then, a green (G) pattern, is formed on part of the first substrate 700 and part of the red (R) pattern by a patterning process, in which the green pattern comprises a green major portion 794 covering the red bumps 792 in the green region to have an uneven surface, and green bumps 795 on the major portion 791 of the red pattern in the red region. Then, a blue (B) pattern is formed on part of the first substrate 700 and part of the red (R) pattern by a patterning process. Moreover, a thermal flow process is performed, whereby the first color filter 710 whose partial surfaces have bumps is formed.

Please rewrite the paragraph the paragraph beginning on page 14, line 8, so that it reads as follows:

In Fig. 8, a first substrate 800 and a second substrate 870 opposite thereto are provided. The first substrate 800 can be a thin film transistor (TFT) array substrate and the second substrate 870 can be a glass substrate. Then, a first color filter 810 having uneven surface is formed on the first substrate 800. The first color filter 810 may have three color regions, such as red (R), green (G), and blue (B). As a demonstrative example, referring to Fig. 8, a red (R) pattern comprising a red major portion 891 in the red region, and red bumps 892 and 893 in the green region and the blue region is formed on part of the first substrate 800 by a patterning process. Then, a green (G) pattern is formed on part of the first substrate 800 and part of the red (R) pattern by a patterning

process, in which the green pattern comprises a green major portion 894 covering the red bumps 892 in the green region to have an uneven surface, and green bumps 895 on the major portion 891 of the red pattern in the red region. Then, a blue (B) pattern is formed on part of the first substrate 800 and part of the red (R) pattern by a patterning process. A thermal flow process is further performed, whereby the first color filter 810 whose partial surfaces have bumps is obtained.

Please rewrite the paragraph the paragraph beginning on page 15, line 25, so that it reads as follows:

In Fig. 9, a first substrate 900 and a second substrate 970 opposite thereto are provided. The first substrate 900 can be a thin film transistor (TFT) array substrate and the second substrate 970 can be a glass substrate. Then, a first color filter 910 having uneven surface is formed on the first substrate 900. The first color filter 910 may have three color regions, such as red (R), green (G), and blue (B). As a demonstrative example, referring to Fig. 9, a red (R) pattern comprising a red major portion 991 in the red region, and red bumps 992 and 993 in the green region and the blue region is formed on part of the first substrate 900 by a patterning process. Then, a green (G) pattern is formed on part of the first substrate 900 and part of the red (R) pattern by a patterning process, in which the green pattern comprises a green major portion 994 covering the red bumps 992 in the green region to have an uneven surface, and green bumps 995 on the major portion 991 of the red pattern in the red region. Then, a blue (B) pattern is formed on part of the first substrate 900 and part of the red (R) pattern by a patterning process. A

thermal flow process is further performed, whereby the first color filter 910 whose partial surfaces have bumps is obtained.